

Replacement Sheet 1 of 2
Applicant: Bern, et al.
Title: APPARATUS FOR CONTROLLING
GAS FLOW IN A SEMICONDUCTOR
SUBSTRATE PROCESSING CHAMBER
Serial No. 10/821,310

2/5

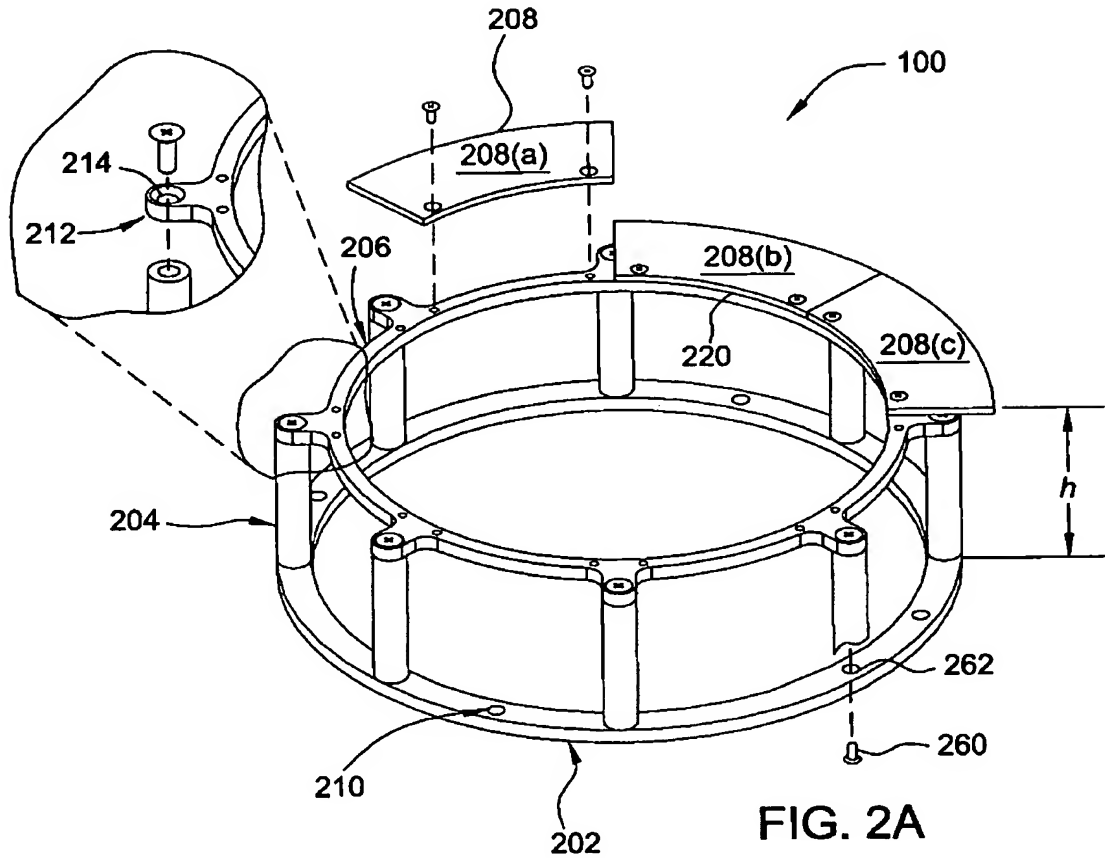


FIG. 2A

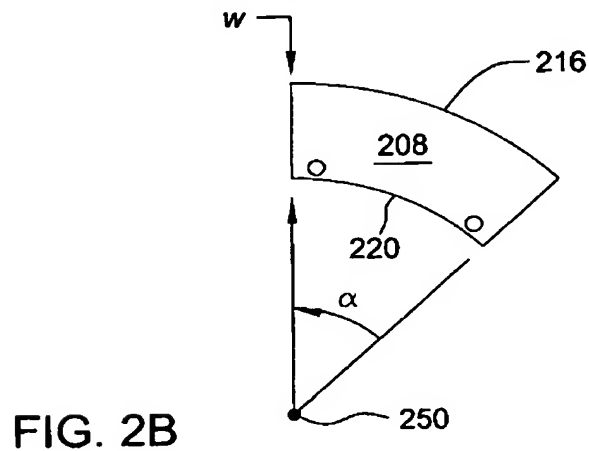


FIG. 2B

Replacement Sheet 2 of 2
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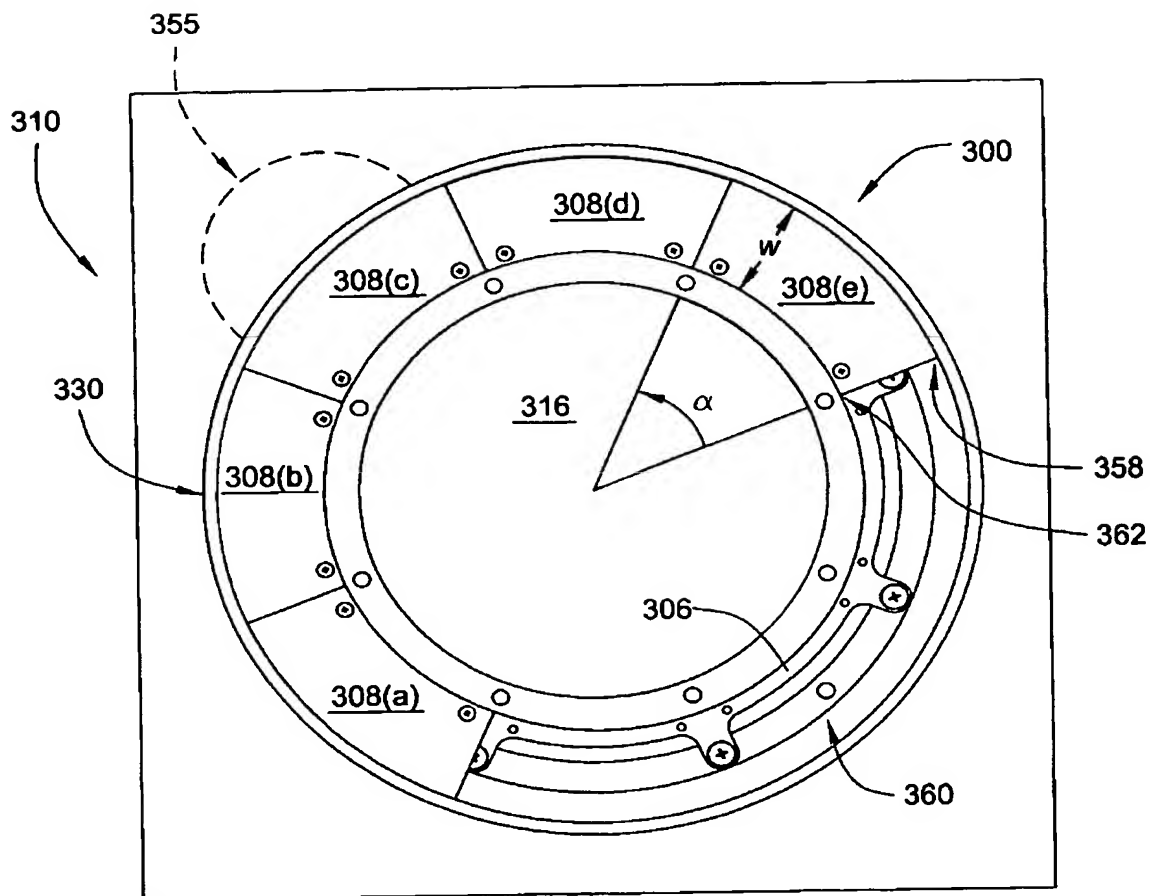


FIG. 3